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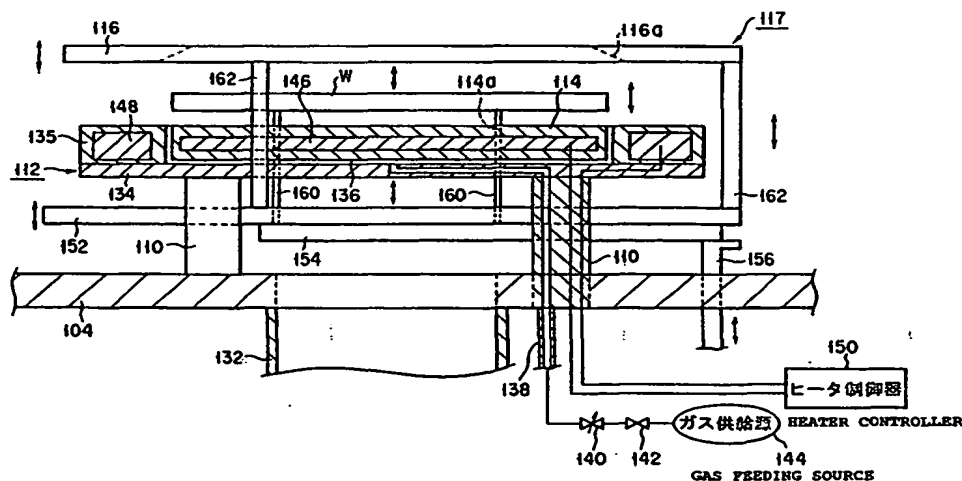
A film deposition apparatus of the present invention includes a container forming a processing chamber for processing a target object, a mounting table which is provided in the processing chamber and on which the target object is mounted, a first heating apparatus provided in the mounting table, for heating the target object mounted on the mounting table, a first gas supply section provided in the container, for supplying processing gas into the processing chamber, the processing gas forming a high-melting-point metal-film layer on the target object mounted on the mounting table, a movable clamp for clamping a periphery of the target object and holding the target object on the mounting table, a second heating apparatus formed separately from the clamp, for heating the clamp indirectly, a gas flow path formed between the clamp and the second heating apparatus when the clamp is moved to a position where the clamp clamps the target object, and a second gas supply section for causing backside gas to flow into the gas flow path.

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<p>(21) 国際出願番号 PCT/JP00/00173</p> <p>(22) 国際出願日 2000年1月17日(17.01.00)</p> <p>(30) 優先権データ 特願平11/9529 1999年1月18日(18.01.99) JP</p> <p>(71) 出願人 (米国を除くすべての指定国について) 東京エレクトロン株式会社 (TOKYO ELECTRON LIMITED)[JP/JP] 〒107-8481 東京都港区赤坂五丁目3番6号 Tokyo, (JP)</p> <p>(72) 発明者; および (75) 発明者/出願人 (米国についてのみ) 田中 澄(TANAKA Sumi)[JP/JP] 〒400-0062 山梨県甲府市池田1-7-34 Yamanashi, (JP) 米田昌剛(YONEDA, Masatake)[JP/JP] 〒409-3866 山梨県中巨摩郡昭和町西条2000 グローブハウス301 Yamanashi, (JP)</p> <p>(74) 代理人 鈴江武彦, 外(SUZUYE, Takehiko et al.) 〒100-0013 東京都千代田区霞が関3丁目7番2号 鈴榮内外國特許法律事務所内 Tokyo, (JP)</p>		<p>(81) 指定国 KR, SG, US</p> <p>添付公開書類 国際調査報告書</p>

(54) Title: **FILM FORMING DEVICE**

(54) 発明の名称 成膜装置



(57) Abstract

A film forming device, characterized by comprising a container forming a processing chamber in which an object is processed, a loading table which is provided in the processing chamber and on which the object is loaded, a first heating device which is provided on the loading table and heats the object loaded on the loading table, a first gas feeding part which is provided in the container and feeds into the processing chamber a processing gas for forming a metallic film layer with high melting point on the object loaded on the loading table, a movable clamp holding the object on the loading table by pressing the peripheral part of the object, a second heating device which is formed separately from the clamp and indirectly heats the clamp, a gas flow path formed at least between the clamp and the second heating device when the clamp is moved to a position where it presses the object, and a second gas feed part feeding a back side gas to the gas flow path.